

FORM: PTO-1449 (REV: 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Atty Docket No: 1999-1335.01/US	Serial No: 10/786,348 Not Assigned
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))		Applicant: Scott J. DeBoer et al.	
(use several sheets if necessary)		Filing Date: February 24, 2004	Group: 2814 Not Assigned

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass
HP	4,656,732	04/14/1987	Teng et al.	438	639
	5,338,700	08/16/1994	Dennison et al.	437	60
	5,401,681	03/28/1995	Dennison	437	60
	5,834,845	11/10/1998	Stolmeijer	257	752
	5,843,830	12/01/1998	Graettinger et al.	438	396
	5,844,771	12/01/1998	Graettinger et al.	361	303
	5,869,861	02/09/1999	Chen	257	306
	5,956,594	09/21/1999	Yang et al.	438	396
	5,989,952	11/23/1999	Jen et al.	438	253
	6,046,093	04/04/2000	DeBoer et al.	438	396
	6,100,137	08/08/2000	Chen et al.	438	253
	6,127,260	10/03/2000	Huang	438	253
	6,140,172	10/31/2000	Parekh	438	238
	6,168,984	01/02/2001	Yoo et al.	438	239
	6,187,624	02/13/2001	Huang	438	253
	6,221,711	04/24/2001	Roberts et al.	438	239
	6,251,726	06/26/2001	Huang	438	253
	6,300,191	10/09/2001	Yu et al.	438	253
HP	6,507,064	01/14/2003	Tang et al.	257	306

FOREIGN PATENT DOCUMENTS

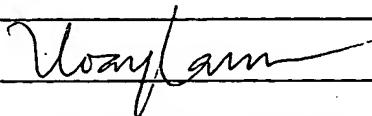
Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
	AT					<input type="checkbox"/>	<input checked="" type="checkbox"/>
	AU					<input type="checkbox"/>	<input checked="" type="checkbox"/>

Initial

OTHER REFERENCES (including author, title, date, pertinent pages, etc.)

HP	AV	Related application entitled: "REDUCED ASPECT RATIO DIGIT LINE CONTACT PROCESS FLOW USED DURING THE FORMATION OF A SEMICONDUCTOR DEVICE", by Brent A. McClure, Micron Technology, Inc., Serial No. 09/765,885, filed January 16, 2001.
	AW	
	AX	

Examiner:



Date Considered:

12/21/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.